

WHAT IS CLAIMED IS:

1. A method of manufacturing an envelope which includes a first substrate, a second substrate opposed to the first substrate, and a space defining member which is located between the first substrate and the second substrate and has a substantially plate shape, the method comprising:

applying a tension to the space defining member;

10 fixing the space defining member to which the tension is applied to the first substrate; and

releasing the tension from the space defining member fixed to the first substrate,

wherein in the fixing of the space defining member to the first substrate, a fixing point of the space defining member to the first substrate is located between points at which the tension is exerted.

20 2. A method of manufacturing an envelope according to claim 1, wherein in the applying of the tension to the interval specifying member, a base of the spacing defining member is located at the point at which the tension is exerted.

25

3. A method of manufacturing an envelope according to claim 1, wherein in the applying of the

tension to the spacing defining member, an auxiliary support member connected with a base of the space defining member is located at the point at which of the tension is exerted.

5

4. A method of manufacturing an electron beam apparatus which includes a first substrate having a plurality of electron-emitting devices on a surface thereof, a second substrate which is opposed to the first substrate and in which an electrode that controls electrons emitted from the plurality of electron-emitting devices is formed, and at least one space defining member which is located between the first substrate and the second substrate and has a substantially plate shape, the method comprising:

15 applying a tension to the space defining member;

 fixing the space defining member to which the tension is applied to the first substrate; and

20 releasing the tension from the space defining member fixed to the first substrate,

 wherein in the fixing of the spacing defining member to the first substrate, a fixing point of the space defining member to the first substrate is located between points at which the tension is exerted.

25

5. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member, a base of the space defining member is located at the
5 points at which the tension is exerted.

6. A method of manufacturing an electron beam apparatus according to claim 4, wherein in the applying of the tension to the space defining member,
10 an auxiliary support member connected with a base of the space defining member is located at the point at which the tension is exerted.

7. A method of manufacturing an electron beam
15 apparatus according to claim 4, wherein in the applying of the tension to the space defining member, the tension is applied by a spacer conveying unit.

8. A method of manufacturing an electron beam
20 apparatus according to claim 4, wherein in the applying of the tension to the space defining member, the tension is applied by a tension applying unit.

9. A method of manufacturing an electron beam
25 apparatus according to claim 4, wherein the interval specifying member has a base of an insulating property.

10. A method of manufacturing an electron beam apparatus according to claim 4, wherein the space defining member has a surface on which a high resistance film is formed.

5

11. A method of manufacturing an electron beam apparatus according to claim 10, wherein the high resistance film has a sheet resistance of 10^7 [Ω /square] or more and 10^{14} [Ω /square] or less.

10

12. A method of manufacturing an electron beam apparatus according to claim 4, wherein the first substrate further includes a plurality of wirings that electrically connect the plurality of electron-emitting devices and the interval specifying members are located on the wiring.

15